

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Washio et al.
Appl. No.	:	10/560,155
Filed	:	December 9, 2005
For	:	DEVELOPER COMPOSITION FOR RESISTS AND METHOD FOR FORMATION OF RESIST PATTERN
Examiner	:	Le, Hoa Van
Group Art Unit	:	1752

AMENDMENT AND RESPONSE TO OFFICE ACTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **May 29, 2007**, Applicants respectfully request consideration of the following amendments and remarks:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks/Arguments begin on page 5 of this paper.